

Coating 113935

Magnetron sputtered system

$HR(0^\circ, 630-1100 \pm 8\text{nm}) > 99.8\% + R(0^\circ, 480-540\text{nm}) < 10\%$

GDD optimized

fig. 1 reflection, 0°

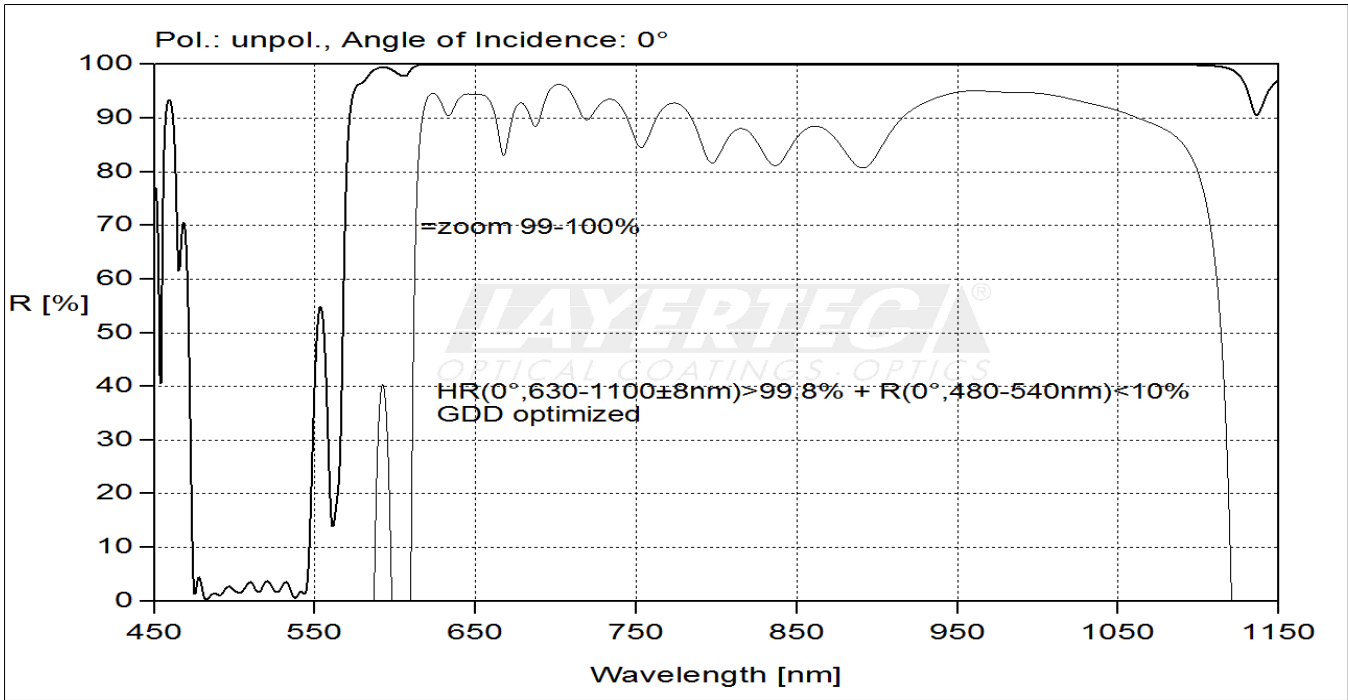


fig. 2 GDD reflection 0°

